

2014/2015 SEMESTER 1 – SEMESTRAL EXAMINATION

Course : Diploma in Electronics, Computer and Communications
Engineering

Module : EG3010 – Microelectronics

Aug/Sep 2014

Time Allowed : 2 hrs

INSTRUCTIONS TO CANDIDATES

1. This exam paper consists of **SEVEN (7)** pages including this page.
2. This examination paper contains 2 sections.

Section A: 2 Questions
Section B: 3 Questions
3. Answer ALL questions in Section A.
Answer ANY 2 questions in Section B.
4. Mask Layout Encoding Table and Stick Diagram Coding Table are provided on Page 7.

SECTION A – ANSWER ALL QUESTIONS (50 Marks)Question 1

- (a) Figure Q1 shows a polysilicon wire segment, not drawn to scale. If it has a sheet resistance of $R_s = R_{SM} \Omega/\square$ and a relative capacitance $0.3 \square C_g$, compute the following:
- resistance of the wire, in terms of R_{SM} . (4 marks)
 - capacitance due to the wire, in terms of $\square C_g$. (4 marks)
 - time taken to travel through this segment of the wire, in terms of τ , where $\tau = R_{sn} * \square C_g$. (4 marks)

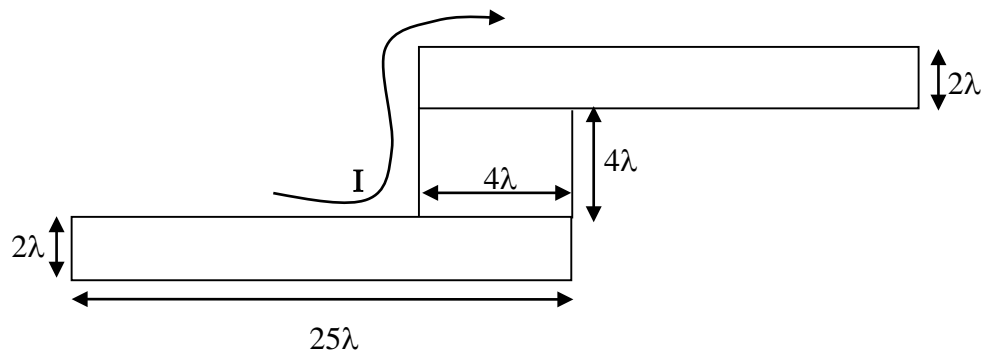


Figure Q1

- (b) Justify the following design rules:
- 2λ poly to poly spacing. (2 marks)
 - 2λ overhanging of polysilicon at transistor gate. (2 marks)
- (c) Latch-up is an inadvertent structure found in CMOS structure.
- Draw the latch-up equivalent circuit and explain what is latch-up. (5 marks)
 - Give two possible consequences when a latch-up occurs. (2 marks)
 - Suggest one method to minimize the occurrence of latch-up. (2 marks)

Question 2

For the CMOS layout shown in Figure Q2,

- (a) draw the corresponding colour-coded stick diagram. (10 marks)
- (b) draw the corresponding transistor level schematic and state the output equation at **Z** of the circuit. (10 marks)
- (c) briefly explain why diffusion is not allowed to cross the substrate-well boundary. (3 marks)
- (d) name the diffusion used to form the well-tie and substrate-tie. (2 marks)

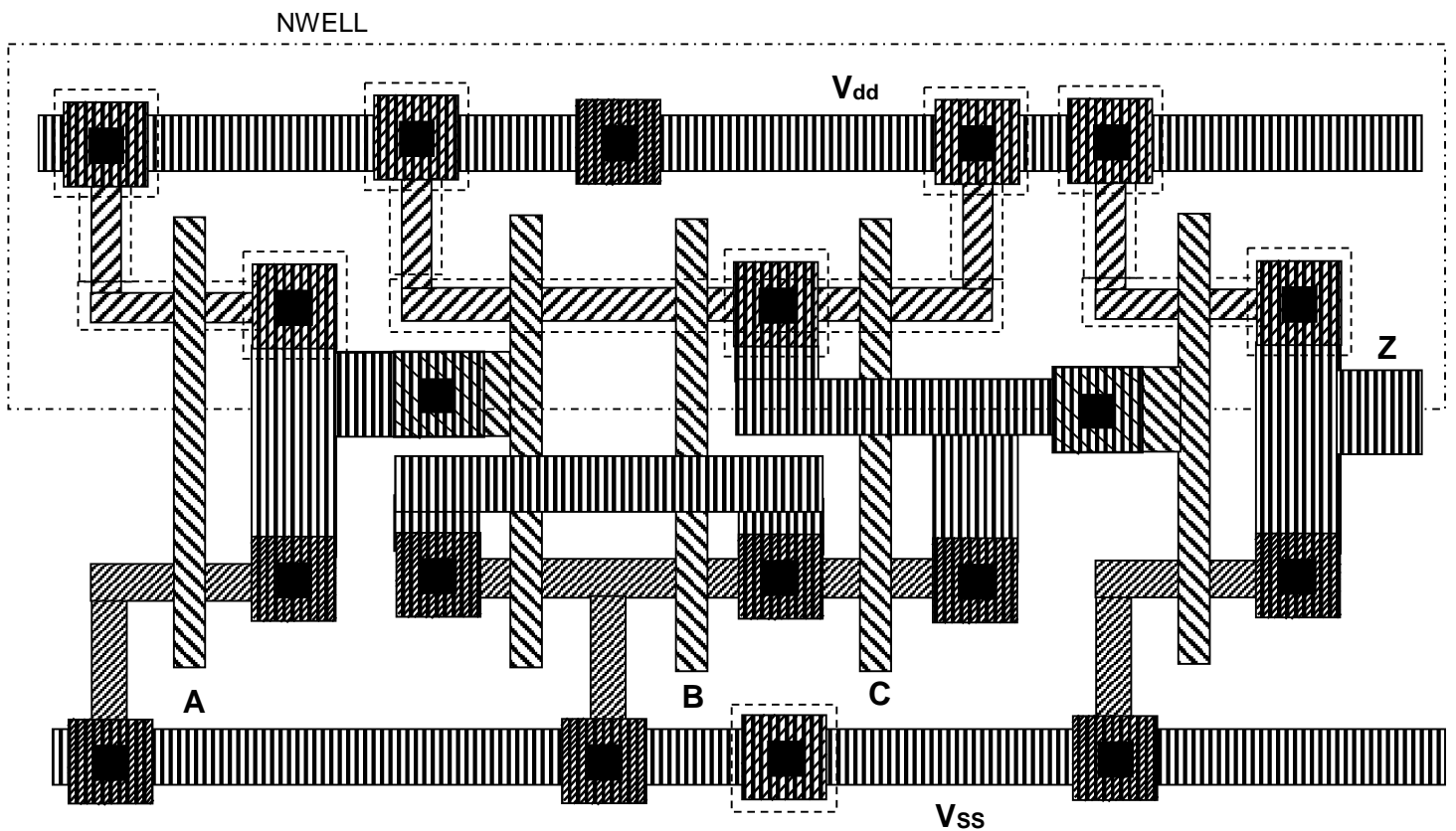


Figure Q2

END OF SECTION A

SECTION B – ANSWER ANY 2 QUESTIONS (50 Marks)

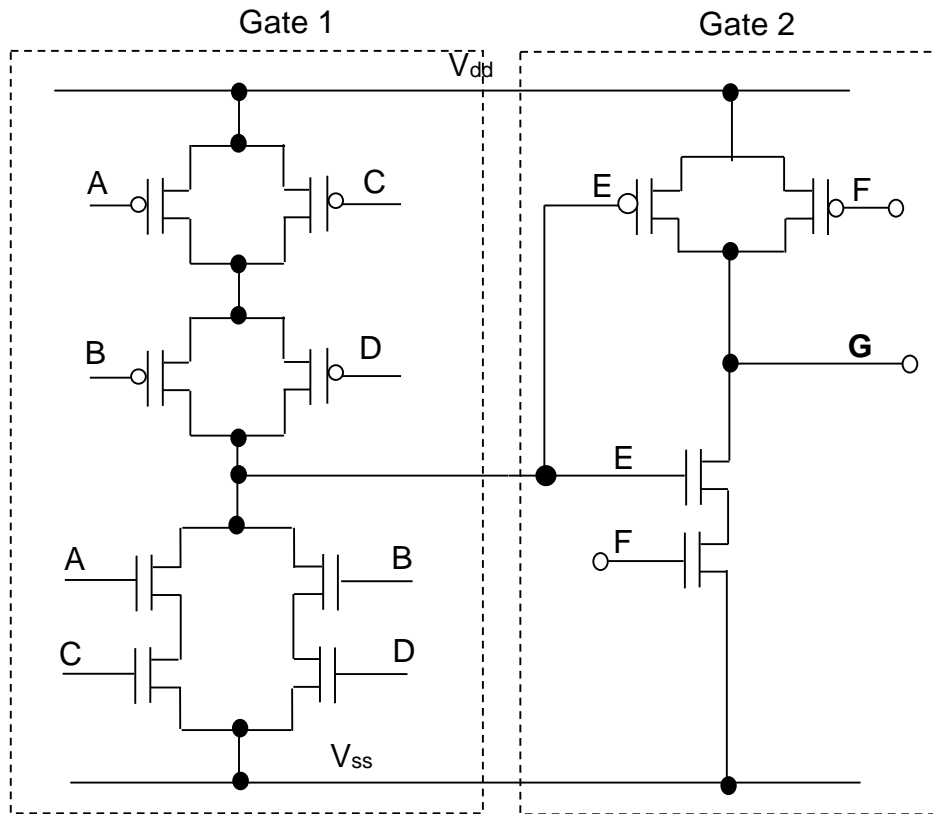
Question 3

Figure Q3

- (a) For the CMOS complex gate shown in Figure Q3, state the boolean equation at point **G**. (5 marks)
- (b) Using the transistor sizes given in Table Q3, calculate the delay time from **D** to **G** for $A = B = F = 1$, $C = D = 0$ for a load of $3C_g$. Give the answer in terms of τ where $\tau = R_{sn} \cdot C_g$ and $R_{sp} \approx 2.5 R_{sn}$. (12 marks)

Gate	Transistor	Length (L)	Width (W)
Gate1	PMOS	2λ	16λ
	NMOS	2λ	2λ
Gate 2	PMOS	2λ	8λ
	NMOS	2λ	4λ

Table Q3

- (c) CMOS devices are known to be ratioless device, yet ratio is applied to the sizing of the various transistors as shown in Table Q3.
- (i) Explain the purposes of having different sized PMOS and NMOS as shown. (2 marks)
 - (ii) Using relevant equations, explain how the size affects the path capacitance? (2 marks)
 - (iii) State 2 trade-offs when using larger transistors compared to smaller ones. (4 marks)

Question 4

- (a) For each of the extrinsic semiconductors (n-type and p-type) :
- (i) name 2 suitable dopants (4 marks)
 - (ii) state the majority carriers found in the semiconductor. (2 marks)
- (b) Draw the layout of an NMOS transistor of Length = 2λ and width = 4λ . Indicate the length and width accordingly. (4 marks)
- (c) Explain how channel length and width of a transistor affects its resistance. Substantiate your answer with relevant equation. (3 marks)
- (d) Explain why dynamic MOS circuits operate faster than static MOS circuits. (4 marks)
- (e) Figure Q4 shows an n-channel P-E logic. Explain its operation in terms of:
- (i) Precharge Phase (4 marks)
 - (ii) Evaluation Phase (4 marks)

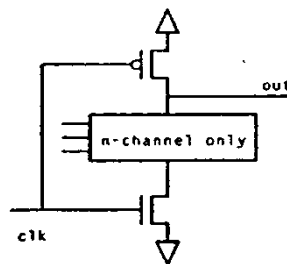


Figure Q4

Question 5

- (a) IC design flow can be divided into 2 major phases namely frontend and backend.
- (i) Name 2 languages commonly used in the frontend for digital circuit design. (2 marks)
 - (ii) Name 4 key processes in the backend phase. (4 marks)
- (b) Explain briefly the purpose of the following in IC design:
- (i) Test benches (2 marks)
 - (ii) Functional simulation (2 marks)
 - (iii) Logic synthesis (2 marks)
- (c) For the codes given in Figure Q5,
- (i) draw the block diagram and label the input and output pins. (4 marks)
 - (ii) explain the functionality of the codes. (6 marks)
 - (iii) the module represents a combinational or sequential circuit? Justify your answer. (3 marks)

```
module exam ( clk, clear, load, data, up_down, oData );  
  
input clk, clear, load, up_down;  
input [7:0] data;  
output [7:0] oData;  
reg [7:0] cnt;  
assign oData = cnt;  
  
always @ (posedge clk)  
begin  
    if (!clear)  
        cnt = 8'h00;  
    else if (load)  
        cnt = data;  
    else if (up_down)  
        cnt = cnt + 1;  
    else  
        cnt = cnt - 1;  
end  
  
endmodule
```

Figure Q5

END OF SECTION B

Mask Layout Encoding Table

LAYERS	MASK LAYOUT ENCODING	CIF LAYER
MONOCHROME		
n-diffusion (n ⁺ active)		ND
Polysilicon		NP
Metal 1		NM
Contact cut		NC
Overglass		NG
Implant		NI
Buried contact		NB
p-diffusion (p ⁺ active)		CAA or CPA
p ⁺ mask		CPP
Metal 2		CMS
VIA		CVA
NWELL		CPW
V _{DD} or V _{SS} CONTACT		CC

FEATURE	FEATURE (MASK) (MONOCHROME)
n-type enhancement transistor	
n-type depletion transistor	
p-type enhancement transistor	

Stick Diagram Encoding Table

Layer	Colour	Stick Encoding
n-diffusion	Yellow outline, Brown within	
p-diffusion	Dark Brown outline, Brown within	
Polysilicon	Green	
Metal 1	Blue	
Metal 2	Red	
Implant	Yellow dotted line	
Contact - Connect Poly to Metal 1 - Connect Diffusion to Metal 1	Black Solid circle	
Via - Connect 2 metals	Black	
*N-well / P-well boundary	Brown dotted line	
*Well tie / Substrate tie	Black Cross	

* only applicable to CMOS process